## **Supporting Information**

## **Boosting Perovskite Light-Emitting-Diodes Performance via**

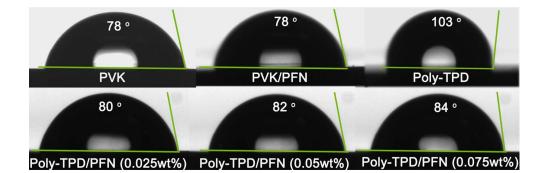
## **Tailoring Interfacial Contact**

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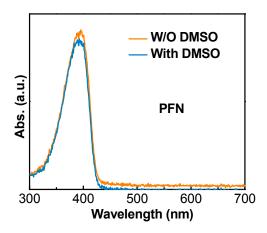
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**Figure S1** Water contact angle images on PVK, PVK/PFN, poly-TPD, and poly-TPD/PFN with different PFN concentration. Contact angle values are depicted in each image.



**Figure S2.** UV-vis absorption spectra of PFN layer before and after DMSO spin coating.

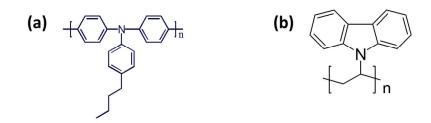


Figure S3 Molecular structures of (a) Poly-TPD, (b) PVK.

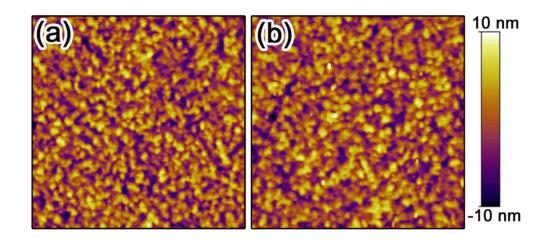


Figure S4 AFM height topography images of poly-TPD films covered (a) without and (b) with PFN coating layer. The RMS values for pristine poly-TPD and poly-TPD/PFN are exactly same with values of ~1.1 nm. The AFM images are 2  $\mu$ m×2  $\mu$ m.

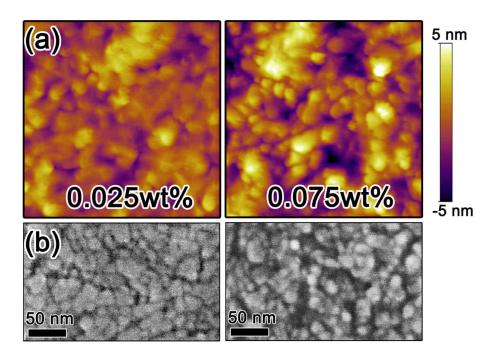
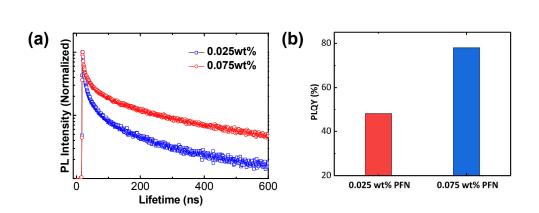


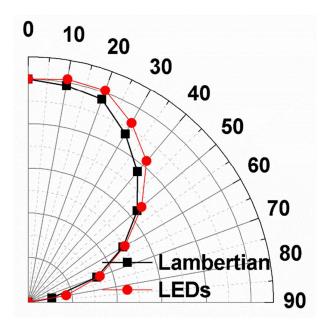
Figure S5 (a) AFM, (b) SEM height topography image of perovskite on poly-TPD/PFN with different PFN concentration. All AFM image sizes are 500  $nm \times 500 nm$ .



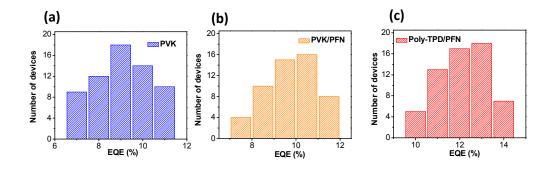
**Figure S6** Photographs of perovskite morphologies deposited on poly-TPD/PFN with different PFN concentration under 365 nm UV light illumination. PFN with concentration from 0.010wt% to 0.100wt% (from left to right).



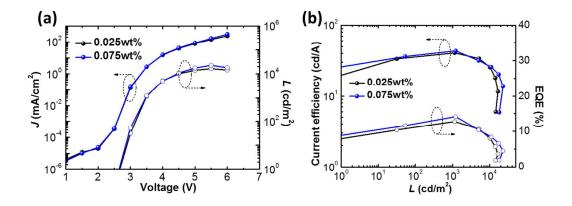
**Figure S7** (a) PL lifetime and (b) PLQY characteristics of perovskite films on poly-TPD/PFN with different PFN concentration.



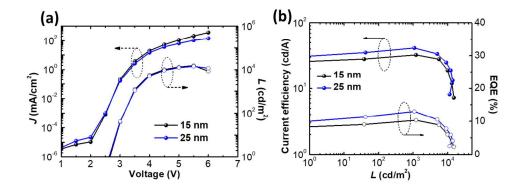
**Figure S8** EL emission angle distribution profile of peroskite LEDs devices compared to the standard Lambertian one.



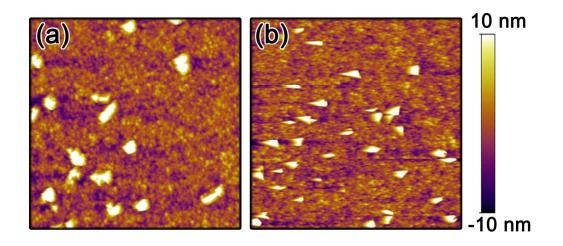
**Figure S9** EQE histogram of ~60 LEDs fabricated on different HTLs. (a) PVK. (b) PVK/PFN. (c) Poly-TPD/FPN. The PFN concentration is 0.050wt%.



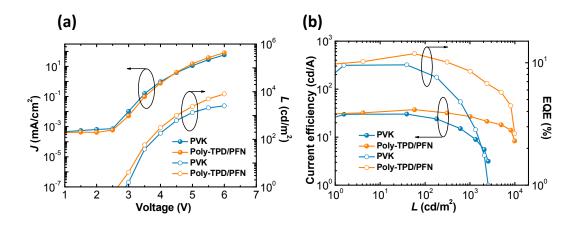
**Figure S10** Electrical output characteristics of the devices based on poly-TPD/PFN HTLs with different PFN thickness. (a) J-V-L characterization; (b) Current efficiency-L -EQE curve.



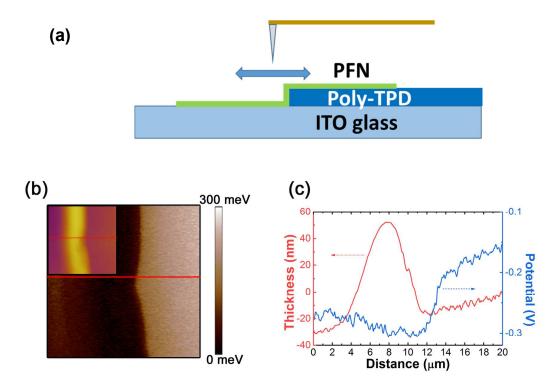
**Figure S11** Electrical output characteristics of the devices based on poly-TPD/PFN (0.050wt%) with different TPBi thickness. (a) J-V-L characterization; (b) Current efficiency-L-EQE curve.



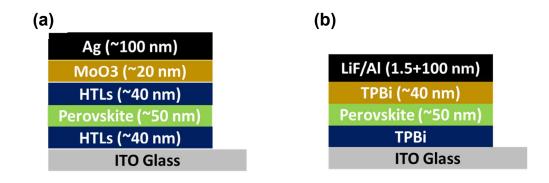
**Figure S12.** AFM height images of perovskite films deposited from the precursor solution with extra PFN (0.02 mg/mL) on (a) PVK (b) poly-TPD/PFN. Here, poly-TPD/PFN layer is deposited by a PFN concentration of 0.050wt%. All AFM sizes are 5  $\mu$ m×5  $\mu$ m.



**Figure S13.** Electrical outputs of LED devices fabricated with PFN in the perovskite precursor solution on PVK or poly-TPD/PFN as HTL. (a) J-V-L curve. (b) CE-L-EQE curve.



**Figure S14** (a) Schematic illustration of experimental set-up for surface potential of ITO/poly-TPD/PFN interlayer probed by SKPM. A ~30-nm-thick poly-TPD layer is deposited on half-side ITO glass, and then completely covered a thin PFN layer to form a distinct interface. (b) SKPM profile of ITO/poly-TPD/PFN interface. Inset shows the height image of the corresponding image. The AFM image size is 20  $\mu$ m by 20  $\mu$ m. (c) Cross-section line profile of height and surface potential images in (b).



**Figure S15** Single carrier device structure of (a) hole-only device and (b) electron-only device. Here, the HTLs are PVK, PVK/PFN, and poly-TPD/PFN. The PFN concentration is 0.05wt%.

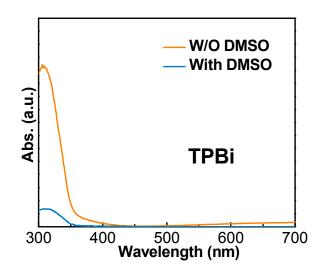


Figure S16. UV-vis absorption spectra of a ~200 nm-thick-TPBi layer with and

without quick DMSO washing.

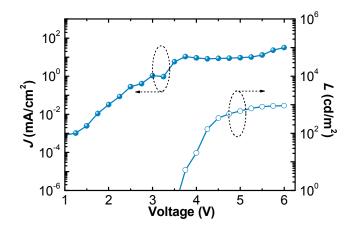


Figure S17. J-V-L curve of device with structure of ITO/perovskite ( $\sim$ 50 nm)/TPBi

(~20 nm)/LiF (~1.5 nm)/Al (~100 nm).

PFN concentration (wt%)	τ <sub>1</sub> (ns)	τ <sub>2</sub> (ns)	τ <sub>3</sub> (ns)	τ <sub>average</sub> (ns)
0	67.8	446.8	7.6	37.8
0.025	79.7	486.8	8.3	53.7
0.050	89.6	510.7	9.4	65.3
0.075	116.5	600.1	11.2	121.6

**Table S1** Summarized PL lifetime of perovskite deposited on poly-TPD/PFN, wherePFN concentration are 0, 0.025wt%, 0.050%wt% and 0.075wt%, respectivley.

Table S2 Electrical output characteristics of the devices based on poly-TPD/PFN as
HTL with different PFN concentration. Here, the thickness of poly-TPD is ~45 nm.

PFN concentration (wt%)	L (cd m <sup>-2</sup> )	$\eta_{p}(\text{Im W}^{-1})$	$\eta_{A}^{-1}$ (cd $A^{-1}$ )	EQE (%)
0.025	16690	36.4	40.5	12.8
0.075	22790	38.8	43.2	13.8

**Table S3** Electrical output characteristics of the devices based on poly-TPD/PFN with different thickness of TPBi. Here, the thickness of poly-TPD is ~45 nm and the PFN concentration is 0.050wt%.

TPBi thickness (nm)	L <sub>max</sub> (cd m <sup>-2</sup> )	$\eta_{p}(\text{Im W}^{-1})$	$\eta_{A}^{}$ (cd $A^{-1}$ )	EQE (%)
15	15120	29.11	32.43	10.34
25	13980	37.10	41.33	13.01